

<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>					Docket Number		Application Number	
					081468-0308582		10/792,267	
					Applicant(s)			
					Klaus SIMON			
Form PTO-1449					Filing Date		Group Art Unit	
					March 4, 2004		1762	
<b>U.S. PATENT DOCUMENTS</b>								
*EXAMINER INITIAL	REF	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
/RY/	A	6,921,615 B2	07/26/2005	Sreenivasan et al.	430	22		
	B	6,719,915 B2	04/13/2004	Willson et al.	216	44		
	C	6,696,220 B2	02/24/2004	Bailey et al.	430	272.1		
	D	6,656,341 B2	12/02/2003	Petersson et al.	205	667		
	E	6,518,189 B1	02/11/2003	Chou	438	706		
	F	6,482,742 B1	11/19/2002	Chou	438	690		
	G	6,375,870 B1	04/23/2002	Visovsky et al.	264	1.31		
	H	6,365,059 B1	04/02/2002	Pechenik	216	52		
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	J	6,309,580 B1	10/30/2001	Chou	264	338		
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	L	5,772,905	06/30/1998	Chou	216	44		
	M	5,512,131	04/30/1996	Kumar et al.	156	655.1		
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	O	2005/0039618 A1	02/24/2005	Heidari et al.	101	368		
	P	2004/0219461 A1	11/04/2004	Chung et al.	430	311		
	Q	2004/0219249 A1	11/04/2004	Chung et al.	425	385		
	R	2004/0209470 A1	10/21/2004	Bajorek	438	689		
	S	2004/0200411 A1	10/14/2004	Willson et al.	118	500		
	T	2004/0192041 A1	09/30/2004	Jeong et al.	438	689		
	U	2004/0169003 A1	09/02/2004	Lee et al.	216	4		
	V	2004/0149367 A1	08/05/2004	Olsson et al.	156	64		
	W	2004/0124566 A1	07/01/2004	Sreenivasan et al.	264	494		
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							YES	NO
/RY/	X	WO 01/79592 A1	10/25/2001	PCT				
/RY/	Y	WO 01/79591 A1	10/25/2001	PCT				
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>								
/RY/	X	Stephen Y. Chou, et al., "Nanoimprint Lithography", J. Vac. Sci. Technol. B 14(6), November/December 1996, pgs. 4129-4133.						
	Y							

EXAMINER	DATE CONSIDERED
/Ren Yan/	10/03/2007
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.	

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↓ /RY/	A	2004/0081798 A1	04/29/2004	Lee et al.	428	141		
	B	2004/0046288 A1	03/11/2004	Chou	264	479		
	C	2004/0036201 A1	02/26/2004	Chou et al.	264	402		
	D	2004/0022888 A1	02/05/2004	Sreenivasan et al.	425	174.4		
	E	2004/0021866 A1	02/05/2004	Watts et al.	356	401		
	F	2004/0009673 A1	01/15/2004	Sreenivasan et al.	438	694		
	G	2004/0005444 A1	01/08/2004	Heidari	428	212		
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	M	2003/0127580 A1	07/10/2003	Ling et al.	249	115		
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	O	2003/0080472 A1	05/01/2003	Chou	264	338		
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V	2002/0093122 A1	07/18/2002	Choi et al.	264	401			
W								
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	REF	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translations	
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	Y							
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	X							
	Y							
	Z							
	AA							

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